

April 16 1986  
ISHM Southern Calif. Symp. LA (CA)

**HIGH PERFORMANCE  
SUBSTRATES  
FOR  
THIN FILM APPLICATIONS**

**HIGH PERFORMANCE SUBSTRATES FOR THIN FILM APPLICATIONS:  
A contemporary survey of materials**

A wide array of substrate materials suitable for thin-film applications will be reviewed. This will include the standard thin-film hybrid 99% + alumina tape-cast ceramics as well as many less common hot pressed ceramics, glasses, glass-ceramics, single crystals, metals, polymers, etc, useful in specialized high performance applications.

The main characteristics pertinent to the thin film technologist will be discussed, viz the surface finishes attainable, the mechanical, machining and wear properties, the physical, chemical electrical and thin film adhesion qualities. These substrate materials have applications in hybrids, very high density interconnect packaging, microwave, high power devices, magnetic thin film heads and many other specialized sensors or devices.

**THIN FILM SUBSTRATES  
A TECHNICAL OVERVIEW**

**THIN FILM SUBSTRATE CRITERIA:**

- \* SUBSTRATE MATERIAL
- \* SURFACE FINISHING TECHNIQUES
- \* TESTING SUBSTRATE PARAMETERS
- \* SUBSTRATE RELATED SUBJECTS:  
ADHESION  
METALLIZING

## CERAMICS

### MANUFACTURING PROCESSES:

- \* TAPE CASTED  
PARTICLES IN POLYMERIC BINDER  
SLURRY + DOCTOR BLADE
- \* DRY PRESSED  
ROOM TEMP, LOW PRESSURE  
LITTLE POLYMERIC BINDER
- \* HIPPED  
NO BINDER  
HEAT + PRESSURE (gas in vessel)  
to 1400°C 30,000 psi
- \* HOT-PRESSING  
NO BINDER  
MECHANICAL PRESSURE  
to 1800°C 80,000 psi

### CRITERIA TO CHOOSE A SUBSTRATE MATERIAL

- \* MECHANICAL  
STRENGTH  
POROSITY  
SURFACE FINISH  
EASE OF MACHINING
- \* THERMAL  
CONDUCTIVITY  
CAPACITY  
EXPANSION COEFFICIENT
- \* CHEMICAL  
STABILITY  
SURFACE STATE (ADHESION)  
THIN FILM COMPATIBILITY
- \* ELECTRICAL  
BULK RESISTIVITY  
DIELECTRIC CONSTANT  
DIELECTRIC BREAKDOWN  
DISSIPATION FACTOR

## CERAMICS

* ALUMINAS	99.5%+ $Al_2O_3$ LUCALOX (Polycrystalline) $Al_2O_3$ -TiC
* BERYLLIAS	99.5%+ BeO
* CARBIDES	$B_4C$ , SiC, TiC
* NITRIDES	AlN, $Si_3N_4$ , Sialon
* TITANIAS	$BaTiO_3$ , $CaTiO_3$ , $TiO_2$
* ZIRCONIAS	$ZrO_2$
* FERRITES	Zr, Ni-Zr, Mn-Zn
* BORIDES	$TiB_2$

## MATERIAL PROPERTIES (HOT PRESSED)

MATERIALS	FLEXURAL STRENGTH (Kg $cm^{-2}$ )
* $BaTiO_3$	1250
* $CaTiO_3$	1500
* BeO	1750
* $Al_2O_3$	3200
* AlN	4000
* SiC	4500
* $Al_2O_3$ -TiC	6000
* $Al_2O_3$ (Sapphire)	7000
* $ZrO_2$	8500

### HARDNESS (Knoops Indentation Test)

MATERIAL	Kg mm <sup>-2</sup> (@ 100g load)
* C (Graphite)	200
* PZT	400
* Fotoceram	500
* Quartz	570
* Mn-Zn (Ferrite)	650
* Zn (Ferrite)	700
* Ni-Zn (Ferrite)	750
* CaTiO <sub>3</sub>	800
* SiO <sub>2</sub>	800
* BaTiO <sub>3</sub>	850
* ThO <sub>2</sub>	1000
* AlN	1200
* BeO	1200
* Al <sub>2</sub> O <sub>3</sub>	1600
* Si <sub>3</sub> N <sub>4</sub>	1850
* Al <sub>2</sub> O <sub>3</sub> -TiC	1850
* Al <sub>2</sub> O <sub>3</sub> (Hot Pressed)	2000
* ZrO <sub>2</sub>	2000
* B <sub>4</sub> C	3000

### DIELECTRIC PROPERTIES

MATERIAL	CONSTANT (1 MHz)	LOSS TANGENT ( $10^{-4}$ )
Polyimide	3.5-3.8	20
Quartz	3.7	1
BN	4.1	13
Glass	4.5-6.0	20
Fotoceram	6.0	40
BeO	6.5	1
Si <sub>3</sub> N <sub>4</sub>	7-10	3
Al <sub>2</sub> O <sub>3</sub> (99.5%+)	9.0	1.5
AlN	9.1	71
Al <sub>2</sub> O <sub>3</sub> (Sapphire)	9.3	1
Si	12	100
GaAs	13	16
YIG	14	2
CaTiO <sub>3</sub>	25 (5 GHz)	5
BaTiO <sub>3</sub>	37 (5 GHz)	5
TiO <sub>2</sub>	100 (5 GHz)	4

## THERMAL CONDUCTIVITY

MATERIAL	W/m C
* Quartz	1.4
* Glass	1.2-2.0
* ZrO <sub>2</sub>	2.0
* Fotoceram	2.5
* BaTiO <sub>3</sub>	3.6
* Zn (Ferrite)	4.0
* Ni-Zn (Ferrite)	4.0
* Mn-Zn (Ferrite)	4.0
* CaTiO <sub>3</sub>	5.2
* ThO <sub>2</sub>	12.0
* Al <sub>2</sub> O <sub>3</sub> -TiC	16.0
* Al <sub>2</sub> O <sub>3</sub>	17.0
* Si <sub>3</sub> N <sub>4</sub>	32.0
* B <sub>4</sub> C	32.0
* BN	44.0
* SiC-Si	50.0
* TiB <sub>2</sub>	70.0
* AlN	125.0
* Al	140.0
* BeO	240.0
* SiC	270.0
* C (Graphite)	800.0
* C (Diamond)	1000.0

### THERMAL COEFFICIENT OF EXPANSION

MATERIAL	ppm/C
* Zerodur	-0.02
* Quartz	0.55
* Glass	1.2
* Si <sub>3</sub> N <sub>4</sub>	3.0
* C (Graphite)	3.2
* Si	3.4
* AlN	4.8
* SiC	5.1
* Al <sub>2</sub> O <sub>3</sub> (Sapphire)	5.6
* Al <sub>2</sub> O <sub>3</sub> (Ceramic)	6.5-8.0
* Al <sub>2</sub> O <sub>3</sub> -TiC	7.8
* TiB <sub>2</sub>	8.2
* Zn (Ferrite)	8.5
* BeO	8.0-9.0
* Ni-Zn (Ferrite)	9.1
* ThO <sub>2</sub>	9.3
* BaTiO <sub>3</sub>	9.6
* Fotoceram	10.0
* ZrO <sub>2</sub>	10.0
* CaTiO <sub>3</sub>	11.5
* Mn-Zn (Ferrite)	12.1
* Cu	18.0
* Al	23.0

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## BULK RESISTIVITY

MATERIAL	OHMS-cm
* Al	$2.7 \times 10^{-6}$
* Cu	$1.7 \times 10^{-6}$
* TiB <sub>2</sub>	$1.0 \times 10^{-5}$
* C (Graphite)	$1.0 \times 10^{-4}$
* Mn-Zn (Ferrite)	1
* SiC	5
* B <sub>4</sub> C	5
* Al <sub>2</sub> O <sub>3</sub> -TiC	10
* Zn (Ferrite)	$>10^3$
* Ni-Fe (Ferrite)	$>10^6$
* Quartz	$>10^9$
* ThO <sub>2</sub>	$>10^{10}$
* ZrO <sub>2</sub>	$>10^{10}$
* AlN	$>10^{11}$
* Al <sub>2</sub> O <sub>3</sub>	$>10^{14}$
* BeO	$>10^{14}$
* BaTiO <sub>3</sub>	$>10^{14}$
* CaTiO <sub>3</sub>	$>10^{14}$
* Polyimide	$>10^{14}$



## SUBSTRATE MEASUREMENTS

- \* CHEMICAL  
ESCA, AUGER, ETC.
- \* DIELECTRIC CONSTANT  
BRIDGE, PHASE-METER, LOCK-IN-AMP
- \* CONDUCTIVITY  
BRIDGE, 4 POINT PROBE, ELECTROMETER
- \* FLATNESS  
OPTICAL FLAT, AIR GAUGE, INTERFEROMETER
- \* CAMBER  
PARALLEL PLATES, INTERFEROMETER
- \* POROSITY, SCRATCHES, PITS & BURRS  
MICROSCOPE, SEM
- \* CRACK DETECTION  
DIES, VAPOR CONDENSATION
- \* SURFACE FINISH  
STYLUS PROFILOMETER, OPTICAL PROFILOMETER
- \* WEAR TEST  
SLIDING PIN ON DISC